

ABSTRACT
FERROMAGNETIC MATERIAL SPUTTERING TARGET

5 Provided is a ferromagnetic material sputtering target comprising a
metal having a composition that Cr is contained in an amount of 20 mol% or
less, Pt is contained in an amount of 5 mol% or more, and the remainder is Co,
wherein the target includes a base metal (A) and, within the base metal (A), a
Co-Pt alloy phase (B) containing 40 to 76 mol% of Pt, and a metal or alloy
10 phase (C), which is different from the phase (B) and is composed of Co or an
alloy comprising Co as a main component. The present invention improves
the leakage magnetic flux to provide a ferromagnetic material sputtering target
that can perform stable discharge with a magnetron sputtering apparatus.